## IAP5 Rec'd PCT/PTO 2 8 MAR 2006

DATE CONSIDERED 06/23/2008

Sheet 1 of I Form PTO-1449 US Dept. of Commerce ATTY DOCKET NO. APPLICATION NO. (REV. 1/06) PATENT & TRADEMARK OFFICE New U.S. National 127516 Stage of 10/573822 PCT/JP2004/015395 INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary) APPLICANTS Ryoji HOSHI et al. FILING DATE March 28, 2006 U.S. PATENT DOCUMENTS Examiner Cite Initials No. Document Number Date Name G.N.R. US 2002/0017234 A1 02/14/2002 ONO ct al. FOREIGN PATENT DOCUMENTS With With Examiner Initials No. Document Number Country English English Abstract Translation /G.N.R./ 2. JP-A-07-223893 08/22/1995 JAPAN x /G.N.R./ 3. JP-A-08-157293 06/18/1996 JAPAN х х /G.N.R./ 4. 02/16/1999 JAPAN x х JP-A-11-043397 /G.N.R./ 5. JP-A-2002-012498 01/15/2002 JAPAN х x /G.N.R./ 6. JP-A-2002-226296 08/14/2002 JAPAN х х GNR/ 7. JP-A-08-330316 12/13/1996 JAPAN х х /G.N.R./ 8 IP-A-11-079889 03/23/1999 JAPAN x x OTHER DOCUMENTS Examiner Cite (Including Author, Title, Date, Pertinent Pages, etc.) Initials No. 9 D.T.J. HURLE et al.: "Mechanism of Swirl Defects Formation in Silicon": Journal of Crystal Growth; Vol. 59; 1982; /G.N.R. pp. 625-643. 06/23/2008

Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; draw line through citation if not in conformance

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and not considered. Include copy of this form with next communication to applicant.

/G. Nagesh Rao/ (06/23/2008)

Date: March 28, 2006

EXAMINER

Examiner: